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PATENT APPLICATION

Cal BIA
6/30/03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q64410

Shinichi KANNA, et al.

Appln. No.: 09/851,113

Group Art Unit: 1752

Confirmation No.: 2319

Examiner: Rosemary E. Ashton

Filed: May 9, 2001

For: POSITIVE RADIATION-SENSITIVE COMPOSITION

AMENDMENT UNDER 37 C.F.R. § 1.111

MAIL STOP NON-FEE AMENDMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated March 13, 2003, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claim 3 without prejudice or disclaimer.

Please enter the following amended claims:

1. (Twice Amended) A positive radiation-sensitive composition comprising:
- (a) a resin whose solubility in an alkali developer increases by the action of an acid;
 - (b) a compound that generates a carboxylic acid having a molecular weight of 100 or less upon irradiation with an actinic ray or a radiant ray;
 - (c) a surfactant; and
 - (d) a solvent,

B'